2025 EUVL and Source Workshop - List of Accepted Papers

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Invited / Submitted	Paper #	Area #	Area Name	First Name	Last Name	Company	Title
Invited	P1	1	Keynote - 1	Allen	Gabor	IBM	IBM Lithography Roadmap and Need for Future Lithography Tools
Invited	P2	1	Keynote - 1	Steven	Carson	Intel	Update on High-NA EUV in process technology development
Invited	P3	1	Keynote - 1	Mark	Gouker	MIT LL	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Invited	P4	2	Keynote - 2	Oscar	Versolato	ARCNL	Research & roadmap for future sources of EUV light and beyond (BEUV)
Invited	P5	2	Keynote - 2	Debbie	Gustafson	Energetiq	We Can Make a Difference – How to Promote Women in Technology
Invited	P6	2	Keynote - 2	Junji	Yumoto	University of Tokyo	Development of Next-Generation Semiconductor Process Technologies for EUV and BEUV under Japan’s “K Program” for Economic Security by JST
Invited	P7	3	Keynote - 3	Robert	Chau	Natcast	EUV and Non-EUV Based Lithography R&D to Extend Semiconductor Device Scaling and Improve Manufacturing Efficiency
Invited	P8	3	Keynote - 3	Bruce	Smith	RIT	EUV multilayer optimization for next-generation EUVL - 13.5nm/11.3nm high-NA and 6.6nm/WW opportunities

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Invited	P11	4	Mask - 1	Stuart	Sherwin	EUV Tech	EUV Absorber Sidewall Metrology with EUV Scatterometry
Invited	P12	4	Mask - 1	Yogev	Baruch	Zeiss	Reduction of Wafer Intra-Field Overlay and CDU Residuals via laser processing of EUV Reticles
Invited	P13	4	Mask - 1	Marcus	Benk	CXRO	Hyper-NA EUV Imaging, and Beyond
Invited	P14	4	Mask - 1	Luke	Long	EUV Tech	HVM-ready EUV zoneplate microscopy for mask defect review
Invited	P15	5	Mask - 2	Ron	Levi	Corning	EXTREME ULE® for EUV Lithography reticles
Submitted	P16	5	Mask - 2	Yunsoo	Kim	Hanyang University	Ion Implantation for Improved Etching and Optical Performance in Next-Generation EUV Mask
Invited	P17	5	Mask - 2	IKEBE	Yohei	Hoya	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Invited	P18	5	Mask - 2	Kevin	Lucas	Synopsys	High NA EUV design to mask stitching enablement

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Invited	P19	5	Mask - 2	Katrina	Rook	Veeco	Advanced Ion Source & Target Developments for EUV Mask Multilayer Deposition
Invited	P21	6	Metrology	Mark	Schattenburg	MIT	High Resolution Imaging and Spectrographic Instruments for 1-10 nm X-ray Astrophysics
Invited	P22	6	Metrology	Brian	Simonds	NIST	Absolute Traceable Electrical Substitution Radiometers for EUV Wavelengths and Beyond
Invited	P23	6	Metrology	Muharrem	Bayraktar	University of Twente	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Submitted	P31	7	Modeling	Kirill	Lezhnin	PPPL	Examining Kinetic Plasma Behavior in EUVL Sources with Particle-In-Cell Simulations
Invited	P32	7	Modeling	Igor	Golovkin	Prism Computations	Plasma Simulations of EUV/x-ray Sources: Radiation Transport and Atomic Physics Models
Invited	P33	7	Modeling	Akira	Sasaki	QST	Atomic model to model EUV emission spectrum and to produce the opacity table of tin
Invited	P41	8	Optics	Vladimir	Liberman	MIT LL	Advanced Blue-X Multilayer Coating Designs Strategies

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Invited	P42	8	Optics	Donis	Flagello	Nikon Research	Beyond One-Size-Fits-All: Tailoring EUV (and BEUV) Optics for HVM Efficiency
Invited	P43	8	Optics	Franck	Delmotte	Université Paris-Saclay	Synthesis and metrology of Cr/Sc-based multilayer mirrors for the water window
Invited	P44	8	Optics	Michael	Patra	Carl Zeiss	Hyper-NA: an EUV system with a numerical aperture of at least 0.75
Invited	P45	8	Optics	Torsten	Feigl	optiXfab	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Invited	P46	8	Optics	Marcelo	Ackermann	University of Twente	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Invited	P51	9	Resist and Patterning 1.1	Oleg	Kostko	CXRO	Advancing EUV Photoresist Development: High-Throughput Screening of Electron-Induced Chemical Transformations
Invited	P52	9	Resist and Patterning 1.1	Myung- Gil	Kim	Sungkyunkwan University	Isomorphic molecular control of Sb based inorganic EUV photoresist for optimized photosensitivity and stability
Invited	P53	9	Resist and Patterning 1.1	Ralph	Dammel	Merck/EMD Electronics	Estimation of Resist Photospeeds for Blue-X Wavelengths

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Invited	P55	10	Resist and Patterning 1.2	Chang-Yong	Nam	Brookhaven National Lab	Organic-Inorganic Hybrid EUV Photoresists Derived from Atomic Layer Deposition Techniques
Invited	P56	10	Resist and Patterning 1.2	Hyun-Dam	Jeong	Chonnam National University	Recent Developments and an Unexpected Discovery in Our Tin-Based Inorganic Molecular Resists for EUV Lithography
Submitted	P57	10	Resist and Patterning 1.2	Chenyun	Yuan	Cornell	EUV photoresists with controlled sequences lead to improved stochastics and the discovery of a novel patterning mechanism
Invited	P58	10	Resist and Patterning 1.2	Rachel	Synder	Dupont	Next-Generation EUV Double Amplification Photoresists From Acid-Catalyzed Chain Unzipping
Invited	P59	10	Resist and Patterning 1.2	Nishiki	Fujimaki	Fujifilm	EUV NTD-CAR performance toward high-NA EUVL
Invited	P60	10	Resist and Patterning 1.2	Alex Robinson	Robinson	IM	The Multi-Trigger Resist - EUV Performance Update
Invited	P61	10	Resist and Patterning 1.2	Anuja	DeSilva	Lam	Dry Resist Patterning Readiness Towards High NA EUV Lithography
Invited	P62	10	Resist and Patterning 1.2	Congque	Dinh	TEL	Advanced Coater/developer Technologies for High-NA EUV Lithography

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Invited	P63	10	Resist and Patterning 1.2	Michael	Tsapatsis	John Hopkins University	Amorphous Zeolitic imidazolate Framework (aZIF) Films for Electron Beam, Extreme UV, and Beyond Extreme UV Lithography Applications
Invited	P64	11	Resist and Patterning 1.3	Sascha	Brose	RWTH	Lab-based EUV interference lithography for large-area nanopatterning towards sub-10 nm resolution
Invited	P65	11	Resist and Patterning 1.3	Bruno	LaFontaine	CXRO	EUV Lithography at The Center for X-Ray Optics
Invited	P66	11	Resist and Patterning 1.3	Hank	Smith	MIT	Replacing EUV with X-ZPAL
Invited	P67	11	Resist and Patterning 1.3	Iacopo	Mochi	PSI	Development of a Next-Generation Interference Lithography End Station at the Swiss Light Source
Invited	P71	12	Source 1	Kentaro	Tomita	Hokkaido University	Increment of EUV radiation and reduction of ion energy of laser-produced Sn EUV-light-source plasmas by controlling initial plasma structure using multiple pre-pulse laser irradiations
Invited	P72	12	Source 1	Hakaru	Mizoguchi	Kyushu university	Plasma Dynamics and Future of LPP-EUV Source for Semiconductor Manufacturing IV
Invited	P73	12	Source 1	Jens	Brunne	Trumpf	The path towards 1.5kW EUV with the CO2 drive laser

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Submitted	P74	12	Source 1	Hideyuki	Sera	Ushio	Diagnostics of Laser-assisted Discharge Tin Plasma EUV source using collective Thomson scattering
Submitted	P75	13	Source 2	Yosuke	Honda	KEK	The Must Light Source
Invited	P76	13	Source 2	Yusuke	Teramoto	Ushio	A compact laser-driven short-wavelength radiation source
Invited	P77	13	Source 2	Takeshi	Higashiguchi	Utsunomiya University	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Submitted	P78	13	Source 2	Jingquan	Lin	Changchun University of Science and Technology,	Enhancement of spectral performance in gadolinium-based BEUV sources
Invited	P79	13	Source 2	David	Reisman	Energetiq	SXR development for metrology, inspection, and process control using a discharge-produced plasma source
Invited	P80	13	Source 2	Jochen	Viekers	ILT	Laser-driven x-ray generation for industrial applications
Invited	P81	14	Source 3	Christian	Gaida	Active Fiber Systems GmbH	2µm fiber laser systems for next generation EUV plasma sources

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Invited	P82	14	Source 3	Jackson	Williams	LLNL	EUV and plasma sources using high energy solid state λ ≈ 2 μm laser drivers
Invited	P83	14	Source 3	Peter	Moulton	MIT LL	Solid state laser drivers for EUV plasma sources
Invited	P84	15	Source 4	Dong Gun	Lee	E-Sol	Why High-Order Harmonic Generation Is the Optimal Source Solution for EUV Mask Review Systems
Invited	P85	15	Source 4	Peter	Kraus	ARCNL	High-Harmonic Generation driven Extreme-Ultraviolet Scatterometry for Nanostructure Characterization
Submitted	P86	15	Source 4	Bastian	Manschwetus	Class 5 Photonics	High repetition rate, high average power XUV sources based on High Harmonic Generation
Invited	P87	15	Source 4	Henry	Keptyn	K&M Labs	Nanoscale Metrologies using Coherent EUV Sources
Invited	P91	16	Supplier Showcase	Henry	Chou	Energetiq	Cost- Effective EUV Light Sources for High-Volume Manufacturing
Invited	P92	16	Supplier Showcase	Matt	Hettermann	EUV Tech	Applications of EUV Metrology Tools

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Submitted	P93	16	Supplier Showcase	Jose	Fonseca	FS Dynamics	Numerical simulations for accelerating productivity and equipment design in semiconductor manufacturing
Invited	P94	16	Supplier Showcase	Victor	Soltwisch	PTB	About X-ray metrology and the aftermath
Invited	P95	16	Supplier Showcase	Andreas	Biermanns - Foeth	Research Instruments	Tools and solutions for actinic EUV metrology
Invited	P96	16	Supplier Showcase	Jacqueline	van Veldhoven	TNO	Studying the interaction of EUV and plasma with scanner construction materials
Invited	P97	16	Supplier Showcase	Meng	Lee	Veeco	2025 EUV and Source Workshop Invited Talk (Tentatiive Title)
Submitted	P101	17	Poster	Soyeong	Heo	Chonnam National University	Synthesis, Characterizations, and Ligand Substitution of a Non-Alkyl Tin Oxo Cluster as an Inorganic Resist for EUV Lithography
Submitted	P102	17	Poster	Seung-Yong	Baek	Chonnam National University	Improved Sensitivity of CNU-TOC-01(4C-C), a Tin-Oxo Cluster-Based EUV Inorganic Resist, via Position-Selective Purification
Submitted	P103	17	Poster	Wonchul	Kee	Chonnam National University	Development of a Monomeric Inorganic Resist (CNU-TIDO-AA) for EUV Lithography

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Submitted	P104	17	Poster	Gahyun	Lee	Chonnam National University	Synthesis and Evaluation of Function-Integrated Inorganic Molecular Resists for EUV Lithography
Submitted	P105	17	Poster	Alessandro	Ruocco	FS Dynamics	Numerical simulations application in semiconductor manufacturing
Submitted	P106	17	Poster	Jochen	Viekers	ILT	Platform to study effects of EUV-induced plasmas
Submitted	P107	17	Poster	Alec	Griffith	PPPL	Laser Diagnostics for EUVL Sources at Princeton Plasma Physics Laboratory
Submitted	P108	17	Poster	Akira	Miyake	Toyama	The development of EUV and soft X-ray optical evaluation systems in TOYAMA
Submitted	P109	17	Poster	Henry	Chou	Energetiq	Energetiq New Products Poster (Tentative Title)